

REMARKS

Claims 1-6 are pending in this application.

By this Amendment, claim 1 is amended to further clarify the features therein, and claims 2-6 are amended to correspond to amended claim 1. No new matter is added by this Amendment. Support for language added to claim 1 may be found at, for example, page 37, line 29 to page 38, line 3; page 22, lines 4-24; and Figs. 2 and 12.

I. The Claims Define Patentable Subject Matter

Claims 1, 2, 4 and 6 are rejected under 35 U.S.C. §102(b) over U.S. Patent No. 5,268,781 (Shigeta); and claims 1 and 3-6 are rejected under 35 U.S.C. §103(a) over GB 1,583,176 (Johnson). These rejections are respectfully traversed.

Claim 1 recites a method for manufacturing a substrate comprising a first slant vacuum deposition step of disposing an inorganic material unidirectionally on an underlayer, and a second slant vacuum deposition step of disposing the inorganic material layer on the substrate unidirectionally, the direction in the second slant vacuum deposition step having an azimuth angle different from at least an azimuth angle of the first slant vacuum deposition step, the direction for disposing the inorganic material unidirectionally in the first or the second inorganic slant vacuum deposition step being along a longitudinal direction of a gap section.

Claim 1 is supported by the specification and Fig. 2. In particular, S_A to S_D , as shown in Fig. 2 of the present application, illustrate disposing the inorganic material in the first or the second inorganic slant vacuum deposition step so that the direction is a longitudinal direction of the gap section. The directions S_A to S_D , along the longitudinal direction of the gap section, correspond to directions S_C and S_D , as shown in Figs. 2 and 12.

Shigeta and Johnson both fail to disclose the features of claim 1, as supported by the specification. That is, neither Shigeta nor Johnson disclose controlling the directions.

By controlling the directions, as recited in claim 1, it is possible to reduce the area in which the inorganic slant vacuum deposition layer is not made. Thus, the inorganic material can be disposed on the gap section more reliably in the first or the second inorganic slant vacuum deposition step. Nowhere is this benefit taught in Shigeta or Johnson.

For the foregoing reasons, Applicants submit claim 1, as well as claims 2-6 dependent therefrom, are not anticipated or rendered obvious by Shigeta and/or Johnson.

Reconsideration and withdrawal of the rejections are thus respectfully requested.

II. Conclusion

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of the pending claims are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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